

REMARKS

Favorable reconsideration is respectfully requested.

The claims are 1-10.

Claims 1-10 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hasegawa et al.

The rejection states that it would have been *prima facie* obvious to one of ordinary skill in the art of photoresist composition to use a monomer having straight-chain acid-labile group in place of the monomer of HASEGAWA et al having a branched-chain acid labile group in the terpolymers of Examples I-24, I-25 and I-26 and reasonably expect same or similar results for a photoresist that has improved resolution, and etch resistance over prior art compositions.

This rejection is respectfully traversed.

In order to demonstrate the unexpectedly excellent performance of the photoresist composition according to claim 1 of the present application in which the monomeric units (a3) of the resinous component (A) were derived from an ester compound between methacrylic acid and a straight-chain alcohol substituted by an alkoxy group according to of claim 1 was compared with a similar but different comparative photoresist composition in which the monomeric units of the resinous component corresponding to the (a3) monomeric units in claim 1 were derived from an ester compound between methacrylic acid and a branched-chain alcohol substituted by an alkoxy group, there is submitted herewith of S. Fujimura, the third named inventor herein.

Thus, to the extent that HASEGAWA constitutes a *prima facie* case of obviousness, such is rebutted by the attached declaration.

No further issues remaining, allowance of this application is respectfully requested.

Respectfully submitted,

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